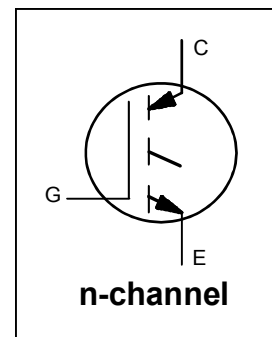


**INSULATED GATE BIPOLAR TRANSISTOR**

$V_{CES} = 1200V$ $I_{C(Nominal)} = 20A$ $T_{J(max)} = 175^{\circ}C$ $V_{CE(on)} \text{ typ} = 1.9V @ I_C = 20A$
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**Applications**

- Medium Power Drives
- UPS
- HEV Inverter
- Welding
- Induction Heating

<b>G</b>	<b>C</b>	<b>E</b>
Gate	Collector	Emitter

<b>Features</b>	<b>Benefits</b>
Low $V_{CE(ON)}$ and switching Losses	High efficiency in a wide range of applications and switching frequencies
Square RBSOA and Maximum Junction Temperature $175^{\circ}C$	Improved Reliability due to rugged hard switching performance and higher power capability
Positive $V_{CE(ON)}$ Temperature Coefficient	Excellent current sharing in parallel operation

<b>Base part number</b>	<b>Package Type</b>	<b>Standard Pack</b>		<b>Orderable part number</b>
		<b>Form</b>	<b>Quantity</b>	
IRG7CH35UEF	Die on film	Wafer	1	IRG7CH35UEF

**Mechanical Parameter**

Die Size	3.937 x 4.826	mm <sup>2</sup>
Minimum Street Width	75	μm
Emitter Pad Size (Included Gate Pad)	See Die Drawing	mm <sup>2</sup>
Gate Pad Size	0.503 x 0.501	
Area Total / Active	19/10	
Thickness	120	μm
Wafer Size	200	mm
Flat Position	0	Degrees
Maximum-Possible Chips per Wafer	1447 pcs	
Passivation Front side	Silicon Nitride	
Front Metal	Al, Si (4μm)	
Backside Metal	Al- Ti - Ni- Ag (1kA°-1kA°-4kA°-6kA°)	
Die Bond	Electrically conductive epoxy or solder	
Reject Ink Dot Size	0.25 mm diameter minimum	

**Maximum Ratings**

	Parameter	Max.	Units
$V_{CE}$	Collector-Emitter Voltage, $T_J=25^\circ\text{C}$	1200	V
$I_C$	DC Collector Current	①	A
$I_{LM}$	Clamped Inductive Load Current ②	80	A
$V_{GE}$	Gate Emitter Voltage	$\pm 30$	V
$T_J, T_{STG}$	Operating Junction and Storage Temperature	-40 to +175	$^\circ\text{C}$

**Static Characteristics (Tested on wafers) .  $T_J=25^\circ\text{C}$** 

	Parameter	Min.	Typ.	Max.	Units	Conditions
$V_{(BR)CES}$	Collector-to-Emitter Breakdown Voltage	1200	—	—	V	$V_{GE} = 0\text{V}, I_C = 100\mu\text{A}$ ③
$V_{CE(sat)}$	Collector-to-Emitter Saturated Voltage	—	1.35	1.60		$V_{GE} = 15\text{V}, I_C = 5\text{A}, T_J = 25^\circ\text{C}$
$V_{GE(th)}$	Gate-Emitter Threshold Voltage	3.0	—	6.0		$I_C = 600\mu\text{A}, V_{GE} = V_{CE}$
$I_{CES}$	Zero Gate Voltage Collector Current	—	2.0	100	$\mu\text{A}$	$V_{CE} = 1200\text{V}, V_{GE} = 0\text{V}$
$I_{GES}$	Gate Emitter Leakage Current	—	—	$\pm 100$	nA	$V_{CE} = 0\text{V}, V_{GE} = \pm 30\text{V}$

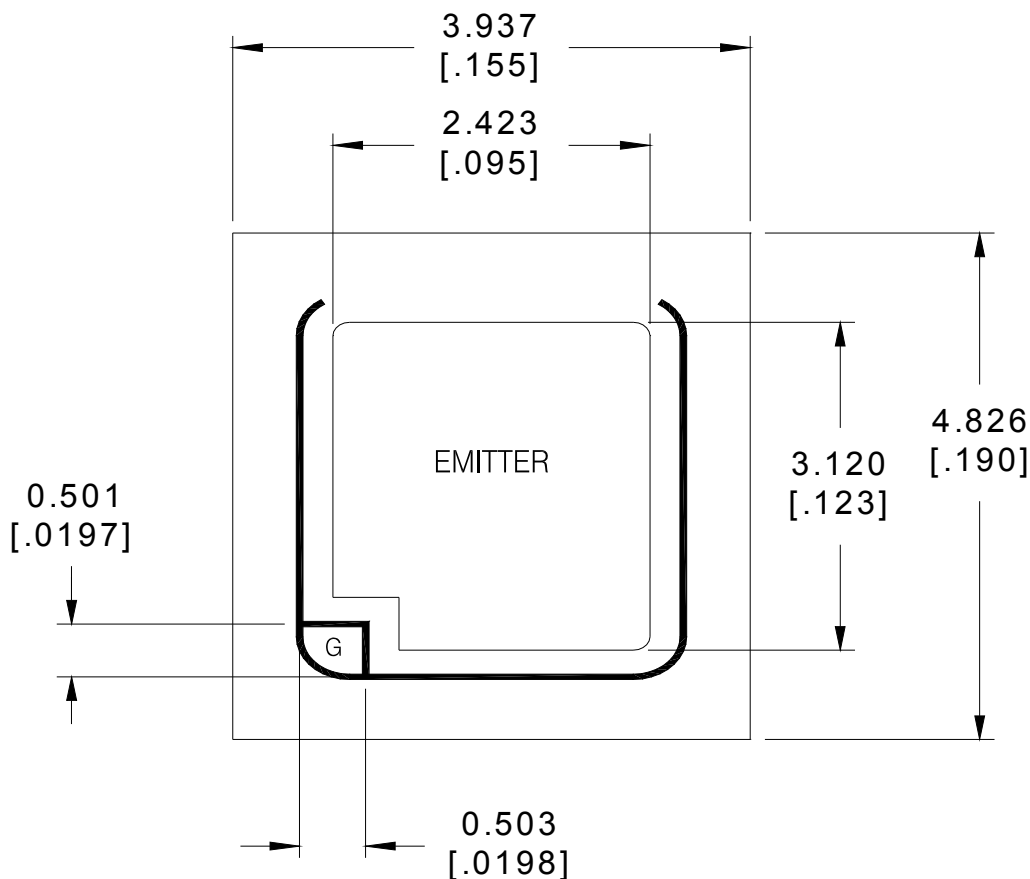
**Electrical Characteristics (Not subject to production test- Verified by design/characterization)**

	Parameter	Min.	Typ.	Max.	Units	Conditions
$V_{CE(sat)}$	Collector-to-Emitter Saturated Voltage	—	1.9	2.2	V	$V_{GE} = 15\text{V}, I_C = 20\text{A}, T_J = 25^\circ\text{C}$ ④
		—	2.4	—		$V_{GE} = 15\text{V}, I_C = 20\text{A}, T_J = 175^\circ\text{C}$ ④
RBSOA	Reverse Bias Safe Operating Area	FULL SQUARE				$T_J = 175^\circ\text{C}, I_C = 80\text{A}$ $V_{CC} = 960\text{V}, V_p \leq 1200\text{V}$ $R_g = 10\Omega, V_{GE} = +20\text{V to } 0\text{V}$
$C_{iss}$	Input Capacitance	—	1905	—	pF	$V_{GE} = 0\text{V}$
$C_{oss}$	Output Capacitance	—	60	—		$V_{CE} = 30\text{V}$
$C_{rss}$	Reverse Transfer Capacitance	—	40	—		$f = 1.0\text{MHz}$ ,
$Q_g$	Total Gate Charge (turn-on)	—	85	—	nC	$I_C = 20\text{A}$
$Q_{ge}$	Gate-to-Emitter Charge (turn-on)	—	15	—		$V_{GE} = 15\text{V}$
$Q_{gc}$	Gate-to-Collector Charge (turn-on)	—	35	—		$V_{CC} = 600\text{V}$

**Switching Characteristics (Inductive Load-Not subject to production test-Verified by design/characterization)**

	Parameter	Min.	Typ.	Max.	Units	Conditions ⑤
$t_{d(on)}$	Turn-On delay time	—	30	—	ns	$I_C = 20\text{A}, V_{CC} = 600\text{V}$ $R_G = 10\Omega, V_{GE}=15\text{V}, L=200\mu\text{H}$ $T_J = 25^\circ\text{C}$
$t_r$	Rise time	—	15	—		
$t_{d(off)}$	Turn-Off delay time	—	160	—		
$t_f$	Fall time	—	80	—		
$t_{d(on)}$	Turn-On delay time	—	25	—		$I_C = 20\text{A}, V_{CC} = 600\text{V}$ $R_G = 10\Omega, V_{GE}=15\text{V}, L= 200\mu\text{H}$ $T_J = 175^\circ\text{C}$
$t_r$	Rise time	—	20	—		
$t_{d(off)}$	Turn-Off delay time	—	200	—		
$t_f$	Fall time	—	200	—		

# Die Drawing


**NOTES:**

1. ALL DIMENSIONS ARE SHOWN IN MILLIMETERS [INCHES].
2. CONTROLLING DIMENSION: MILLIMETERS
3. LETTER DESIGNATION:  
 S = SOURCE    SK = SOURCE KELVIN    E = EMITTER  
 G = GATE      IS = CURRENTSENSE
4. DIMENSIONAL TOLERANCES:  
 BONDING PADS: < 0.635 TOLERANCE = +/- 0.013  
 WIDTH < [.0250] TOLERANCE = +/- [.0005]  
 & > 0.635 TOLERANCE = +/- 0.025  
 LENGTH > [.0250] TOLERANCE = +/- [.0010]  
 OVERALL DIE: < 1.270 TOLERANCE = +/- 0.102  
 WIDTH < [.050] TOLERANCE = +/- [.004]  
 & > 1.270 TOLERANCE = +/- 0.203  
 LENGTH > [.050] TOLERANCE = +/- [.008]
5. DIE THICKNESS = 0.120 [.0047]

REFERENCE: IRG7CH35UB  
 IRG7PH35UPBF  
 IRG7PH35U-EP  
 IRG7PH35UDPBF  
 IRG7PH35UD-EP  
 IRG7PH35UD1PBF  
 IRG7PH35UD1-EP

**Notes:**

- ① The current in the application is limited by  $T_{JMax}$  and the thermal properties of the assembly.
- ②  $V_{CC} = 80\% (V_{CES})$ ,  $V_{GE} = 20V$ ,  $L = 200\mu H$ ,  $R_G = 10\Omega$ .
- ③ Refer to AN-1086 for guidelines for measuring  $V_{(BR)CES}$  safely
- ④ Die Level Characterization
- ⑤ Values influenced by parasitic L and C in measurement

**Additional Testing and Screening**

For Customers requiring product supplied as Known Good Die (KGD) or requiring specific die level testing, please contact your local IR Sales.

**Shipping**

Sawn Wafer on Film. Please contact your local IR sales office for non-standard shipping options

**Handling**

- Product must be handled only at ESD safe workstations. Standard ESD precautions and safe work environments are as defined in MIL-HDBK-263.
- Product must be handled only in a class 10,000 or better-designated clean room environment.
- Singulated die are not to be handled with tweezers. A vacuum wand with a non-metallic ESD protected tip should be used.

**Wafer/Die Storage**

- Proper storage conditions are necessary to prevent product contamination and/or degradation after shipment.
- Note: To reduce the risk of contamination or degradation, it is recommended that product not being used in the assembly process be returned to their original containers and resealed with a vacuum seal process.
- Sawn wafers on a film frame are intended for immediate use and have a limited shelf life.

**Further Information**

For further information please contact your local IR Sales office or email your enquiry to <http://die.irf.com>

Data and specifications subject to change without notice.  
This product has been designed and qualified for Industrial market.  
Qualification Standards can be found on IR's Web site.

International  
**IOR** Rectifier

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